

What is claimed is:

1           1.           A method for sampling a high temperature process stream, comprising  
2   the steps of:  
3           evacuating a low temperature zone of a sampling system using a vacuum pump;  
4           admitting a portion of the high temperature process stream into the low  
5   temperature zone through an orifice;  
6           maintaining a stable vacuum pressure in the low temperature zone; and  
7           introducing a sample from the low temperature zone of the sampling system into  
8   test equipment through a sample introduction valve.

1           2.           The method of claim 1, wherein the orifice has a diameter of between  
2   0.005 inches and 0.025 inches.

1           3.           The method of claim 1, wherein the step of maintaining a stable  
2   vacuum pressure in the low temperature zone includes metering flow to the vacuum  
3   pump.

1           4.           The method of claim 1, wherein the step of maintaining a stable  
2   vacuum pressure in the low temperature zone includes controlling the vacuum pump.

1           5.           The method of claim 1, wherein a temperature of the high temperature  
2   process stream is above a boiling point of a target sample component at the process  
3   stream pressure.

4           6.           The method of claim 1, further comprising the step of maintaining a  
5   temperature of the low temperature zone above a boiling point of a target sample  
6   component at the stable vacuum pressure.

1           7.           The method of claim 1, wherein the test equipment includes a mass  
2   spectrometer.

1           8.           The method of claim 1, wherein the test equipment includes a FT-ICR  
2   mass spectrometer.

1           9.           The method of claim 8, wherein the FT-ICR mass spectrometer  
2   includes a second vacuum pump, and the method further comprises the step of evacuating  
3   with the second vacuum pump a chamber of the FT-ICR to a pressure lower than the  
4   stable vacuum pressure in the low temperature zone.

1           10.          The method of claim 1, wherein the stable vacuum pressure is between  
2   a pressure of the process stream and a high vacuum pressure of a vacuum chamber of the  
3   test equipment.

1           11.          A sampling system for sampling a high temperature process stream to  
2   be tested in an analytical instrument, the sampling system comprising:  
3           an evacuation system for maintaining a low temperature zone of the sampling  
4   system at a vacuum pressure;  
5           a nozzle having an orifice connecting the sample stream with the low pressure  
6   zone of the sampling system; and

7 a sample introduction valve connecting the low temperature zone of the sampling  
8 system with a vacuum chamber of the analytical instrument, the sample introduction  
9 valve being located between the evacuation system and the nozzle.

1 12. The sampling system of claim 11, wherein the analytical instrument is  
2 a mass spectrometer.

1 13. The sampling system of claim 11, wherein the analytical instrument is  
2 an FT-ICR mass spectrometer.

1 14. The sampling system of claim 11, wherein the evacuation system  
2 comprises a vacuum pump.

1 15. The sampling system of claim 14, wherein the evacuation system  
2 further comprises a metering valve for metering an intake of the vacuum pump.

1 16. The sampling system of claim 11, wherein the orifice has a diameter of  
2 between 0.005 inches and 0.025 inches.

1 17. A method for sampling from a gaseous process stream at a process  
2 stream temperature and pressure, the stream having at least one component with a first  
3 boiling point lower than the process stream temperature when at the process stream  
4 pressure, the method comprising the steps of:

5 admitting a gas sample from the process stream through an orifice into a sampling  
6 system, the sampling system having a sampling system temperature lower than the first  
7 boiling point, the sampling system further having a sampling system pressure lower than

8 the process stream pressure, whereby the component in the gas sample has a second  
9 boiling point at the sampling system pressure, the second boiling point being lower than  
10 the sampling system temperature; and

11 introducing a portion of the gas sample into a test instrument chamber.

1 18. The method of claim 17, wherein the step of introducing the portion of  
2 the gas sample into the test instrument chamber includes pulsing a piezoelectric valve.

1 19. The method of claim 17, wherein the orifice is between 0.005 inches  
2 and 0.025 inches in diameter.

1 20. The method of claim 17, further comprising the step of maintaining a  
2 stable vacuum pressure in the sampling system.

1 21. The method of claim 20, wherein the step of maintaining a stable  
2 vacuum pressure in the sampling system includes regulating a vacuum pump throughput.

1 22. The method of claim 20, wherein the step of maintaining a stable  
2 vacuum pressure in the sampling system includes regulating a valve that meters flow  
3 through a vacuum pump.